

Anatech Pd/Au Sputter Coating Procedure – Takes about 3-5 minutes to Complete.

- 1) Verify control settings –
 - a. Main Power Switch - Off
 - b. Voltage Setting – 0
 - c. Voltage Control – Off
 - d. Gas On/Off Switch – Off
 - e. Pulse – Off
 - f. Rotation – Off
- 2) Open vent valve and allow ~30 seconds for the chamber to reach atmosphere. The vent valve is located on the lower right side of the machine.
- 3) Open Lid and place sample on rotating stage.
- 4) Close vent valve, do not over tighten the valve.
- 5) Close Lid and turn the Main Power Switch On
- 6) Allow chamber to pump below 50 mT (\approx 1 minute)
- 7) Turn Gas On/Off Switch On, adjust Argon Fine Gas Control Valve until a steady state 60-80 mT chamber pressure is achieved.
- 8) Turn Rotation control On (Rotation Speed is 2 rpm).
- 9) Set the process timer to 120s (Deposition Rate \approx 2.5 nm/min)
- 10) Turn the Voltage Switch On and set the Manual/Auto Switch to the Auto position.
- 11) Turn the Voltage Control clockwise to achieve an emissions current of 15 mA. Readjust during the process sequence if necessary, range is typically 3-5 (3-5 kV).
- 12) When processing is complete, adjust the control settings as follows –
 - a. Main Power Switch - Off
 - b. Voltage Setting – 0
 - c. Voltage Control – Off
 - d. Gas On/Off Switch – Off
 - e. Pulse – Off
 - f. Rotation – Off
- 13) Open vent valve and allow ~30 seconds for the chamber to reach atmosphere. The vent valve is located on the lower right side of the machine.
- 14) Open Lid and remove sample from rotating stage.
- 15) Close vent valve, do not over tighten the valve.
- 16) Close Lid and turn the Main Power Switch On. Allow chamber to pump below 50 mT and then turn Off the Main Power Switch.